

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	278	saga-k\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
2	BRS	L2	21343	watanabe-h\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	3600	azuma-t\$.in.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
4	BRS	L4	129651	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or treat or treating or treated or treatment or cleanser) adj5 (wafer or silicon or semiconductor or substrate or electronic or micromachine or integrated adj3 circuit)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
5	BRS	L5	216034	(decontaminate or decontaminating or decontaminated or decontamination or flush or flushing or flushed or immerse or immersing or immersed or immersion or dip or dipping or dipped or soak or soaking or soaked or strip or stripping or stripper or stripped or etch or etching or etched or etchant or wash or washing or washed or spray or spraying or sprayed) adj5 (wafer or silicon or semiconductor or substrate or electronic or micromachine or integrated adj3 circuit)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6	25213	11 or 12 or 13	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
7	BRS	L7	311327	14 or 15	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
8	BRS	L8	37193	(supercritical or critical or densified) adj5 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or nitrogen or "N2" or "N.sub.2" or "CO.sub.2" or ammonia or "NH3" or "NH.sub.3" or alcohol or diethyl adj3 ether or benzene or water or "H.sub.2O" or "H2O")	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
9	BRS	L9	596317	(tertiary adj3 amine or trimethyl adj3 amine or trimethylamine or trialkyl adj3 amine or trialkylamine or triethyl adj3 amine or triethylamine or tripropylamine or tripropyl adj3 amine or tri adj3 butylamine or tributyl adj3 amine or tripentyl adj3 amine or tri adj3 iso adj3 butyl adj3 amine or tri adj3 pentylamine or tri adj3 pentyl adj3 amine or tri adj3 iso adj3 amyl adj3 amine or tri adj3 hexyl adj3 amine or tri adj3 heptyl adj3 amine or tri adj3 octyl adj3 amine or tri adj3 ethyl adj3 hexyl amine)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
10	BRS	L10	596439	(tri adj3 decyl amine or tri adj5 amine or tri adj3 dodecyl adj3 amine or tetra adj3 methyl adj3 diamine or pentamethyl adj3 diethylene adj3 triamine or (diethyl or dimethyl) adj3 (ethyl or isopropyl or butyl or octyl or decyl or dodecyl or tetradecyl or hexadecyl or octadecyl or cyclohexyl) adj3 amine or diethanol adj3 amine or triethanol adj3 amine or triisopropanol adj3 amine or dimethyl adj3 ethanol adj3 amine or diethyl adj3 ethanol adj3 amine or dibutyl adj3 ethanolamine or dimethyl adj3 propanol adj3 amine or aniline or dimethyl adj3 toluidine)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
11	BRS	L11	125062	(dimethyl adj3 aniline or diethyl adj3 aniline or diethyl adj3 toluidine or toluidine or dimethyl adj3 benzyl adj3 amine or diethyl adj3 benzyl adj3 amine or dibenzyl adj3 hydroxyl adj3 amine or pyrrolidine or NMP or N- methyl adj3 pyrrolidine or ethyl adj3 pyrrolidine or methyl adj3 piperidine or ethyl adj3 piperidine or piperazine or methyl adj3 morpholine or morpholine or methyl adj3 pyrrole or ethyl adj3 pyrrole or diazabicyclo adj3 octane or hydroxy adj3 ethyl adj3 piperidine or hydroxyl adj3 ethyl adj3 morpholine or hydroxyethyl adj3 pyrrole or diazabicyclo adj3 nonane)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L12	667976	19 or 110 or 111	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
13	BRS	L13	366633	("134"/\$ or "438"/\$ or "216"/\$ or "510"/\$ or "252"/\$).cccls.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
14	BRS	L14	640	17 same 18	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L16	184	114 and 112	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
16	BRS	L15	10	114 same 112	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
17	BRS	L17	93	116 and 113	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
18	BRS	L18	534	(supercritical or critical or densified) adj5 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or nitrogen or "N2" or "N.sub.2" or "CO.sub.2" or ammonia or "NH3" or "NH.sub.3" or alcohol or diethyl adj3 ether or benzene or water or "H.sub.2O" or "H2O") same (dry or drying) same (wafer or silicon or semiconductor or substrate or electronic or micromachine or integrated adj3 circuit)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
19	BRS	L19	231	(supercritical or critical or densified) adj5 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or nitrogen or "N2" or "N.sub.2" or "CO.sub.2" or ammonia or "NH3" or "NH.sub.3" or alcohol or diethyl adj3 ether or benzene or water or "H.sub.2O" or "H2O") same (gaseous or gas or vapor or vapour) same (dry or drying) same (wafer or silicon or semiconductor or substrate or electronic or micromachine or integrated adj3 circuit)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
20	BRS	L20	219102	(decontaminate or decontaminating or decontaminated or decontamination or flush or flushing or flushed or immerse or immersing or immersed or immersion or dip or dipping or dipped or soak or soaking or soaked or strip or stripping or stripper or stripped or etch or etching or etched or etchant or wash or washing or washed or spray or spraying or sprayed or rinse or rinsing or rinsed) adj5 (wafer or silicon or semiconductor or substrate or electronic or micromachine or integrated adj3 circuit)	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
21	BRS	L21	81	119 and 113	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
22	BRS	L22	0	16 and 118	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
23	BRS	L23	0	16 and 119	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
24	BRS	L24	38	119 and 112 and 113	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
25	BRS	L25	995	(supercritical or critical or densified) adj5 (fluid or liquid or gas or carbon adj3 dioxide or "CO2" or nitrogen or "N2" or "N.sub.2" or "CO.sub.2" or ammonia or "NH3" or "NH.sub.3" or alcohol or diethyl adj3 ether or benzene or water or "H.sub.2O" or "H2O") same ((gaseous or gas or vapor or vapour) adj3 (phase or state) same (supercritical or critical) adj3 (phase or state))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B
26	BRS	L26	15	125 same 17	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B

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27	BRS	L27	10432	(minimize or minimizing or minimized or reduce or reducing or reduced or reduction or avoid or avoiding or avoided or prevent or prevented or preventing or eliminate or eliminating or eliminated or elimination or decrease or decreasing or decreased) adj10 (liquid) adj3 (contact or phase)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
28	BRS	L28	63	17 and 18 and 127	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
29	BRS	L29	13013	(minimize or minimizing or minimized or reduce or reducing or reduced or reduction or avoid or avoiding or avoided or prevent or prevented or preventing or eliminate or eliminating or eliminated or elimination or decrease or decreasing or decreased or inhibit or inhibiting or inhibited or inhibition) adj10 ((liquid) adj3 (contact or phase) or liquify or liquified or liquification)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
30	BRS	L30	88	17 and 18 and 129	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B